

Please amend the following claims as indicated:

1. (Amended) A chrome plated part comprising a substrate having a crack-free chrome layer on a surface thereof, the crack-free chrome layer having compressive residual stress of 100 MPa or more and being formed by electroplating.

*C6* 2. (Amended) A chrome plated part comprising a substrate having a crack-free chrome layer on a surface thereof, the crack-free chrome layer having compressive residual stress of 150 MPa or more and being formed by electroplating.

*C6* 3. (Amended) A chrome plated part according to claim 2, wherein the crack-free chrome layer has a crystal grain size of 9 nm or more.

*C7* 4. (Amended) A chrome plated part according to claim 1, wherein the crack-free chrome layer is a lower chrome layer and the chrome plated part further comprises a cracked upper chrome layer which is formed on the lower chrome layer by electroplating.

*C7* 5. (Amended) A chrome plated part according to claim 5, further comprising at least one intermediate chrome layer which is formed between the lower chrome layer and the upper chrome layer by electroplating.

*C8* 6. (Amended) A chrome plating method comprising the step of conducting electroplating of a work in a chrome plating bath by application of a pulse current, the chrome plating bath containing organic sulfonic acid, to thereby deposit a crack-free chrome layer on a surface of the work, the crack-free chrome layer having compressive residual stress of 100 MPa or more.

*C8* 7. (Amended) A chrome plating method comprising the step of conducting electroplating of a work in a chrome plating bath by application of a pulse current, the chrome plating bath containing organic sulfonic acid, to thereby deposit a crack-free chrome layer on a surface of the work, the crack-free chrome layer having compressive residual stress of 150 MPa or more.